

**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q80708

Ryu OHTAGURO, et al.

Appln. No.: 10/808,540

Group Art Unit: 1756

Confirmation No.: 4872

Examiner: Stephen D. ROSASCO

Filed: March 25, 2004

For: SUBSTRATE FOR PHOTOMASK, PHOTOMASK BLANK AND PHOTOMASK

**AMENDMENT UNDER 37 C.F.R. § 1.111**

**MAIL STOP AMENDMENT**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated January 18, 2007, please amend the above-identified application as follows on the accompanying pages.

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